

Interference Search

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L16	4	vcsl and (substrate or wafer or carrier or base or plate) same (oxidiz\$4 or oxidat\$4) and temperature and (gas same (substrate or wafer or carrier or base or plate)) and (layer or film) same stack and (oxidiz\$4 or oxidat\$4) near4 (layer or film) and (heat\$4 or thermal or anneal \$4) same (substrate or wafer or carrier or base or plate) and ((gallium near arsenide) or "GaAs") and chamber .clm.	US-PGPUB	OR	ON	2009/05/21 10:06

5/ 21/ 09 10:19:08 AM

C:\ Documents and Settings\ mharrison1\ My Documents\ EAST\ workspaces
\ 10522505.wsp